

15.45/6059

Version With Markings to Show Changes Made

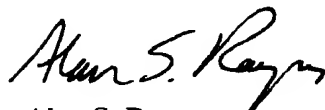
Claim 26 was amended as follows:

26. (amended) A method as in claim 19, wherein the dielectric layer is formed using high density plasma chemical vapor deposition.

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It is believed that no fees are due relating to this submission, however, if fees are due relating to this submission, please charge them to deposit account no. 50-0585. A copy of this paper is enclosed.

Respectfully submitted,



Alan S. Raynes

Reg. No. 39,809

KONRAD RAYNES & VICTOR LLP

315 South Beverly Drive, Suite 210

Beverly Hills, CA 90212

(310) 556-7983 (tele general)

(310) 871-8448 (tele direct)

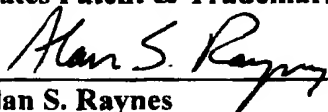
(310) 556-7984 (fax)

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Alan S. Raynes5/29/02
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